United States Patent [19]
Suwa

[11] **Des. 254,656**
[45] ** **Apr. 8, 1980**

[54] **DEPTH MICROMETER**

[75] Inventor: **Hiroaki Suwa,** Hiroshima, Japan

[73] Assignee: **Mitutoyo Mfg. Co., Ltd.,** Tokyo, Japan

[**] Term: **14 Years**

[21] Appl. No.: **883,036**

[22] Filed: **Mar. 2, 1978**

[30] **Foreign Application Priority Data**

Oct. 17, 1977 [JP] Japan 52-040866

[51] **Int. Cl.** .... **D10—04**
[52] **U.S. Cl.** **D10/73;** D10/70
[58] **Field of Search** .... D10/46, 70, 73; 33/169 B, 170

[56] **References Cited**

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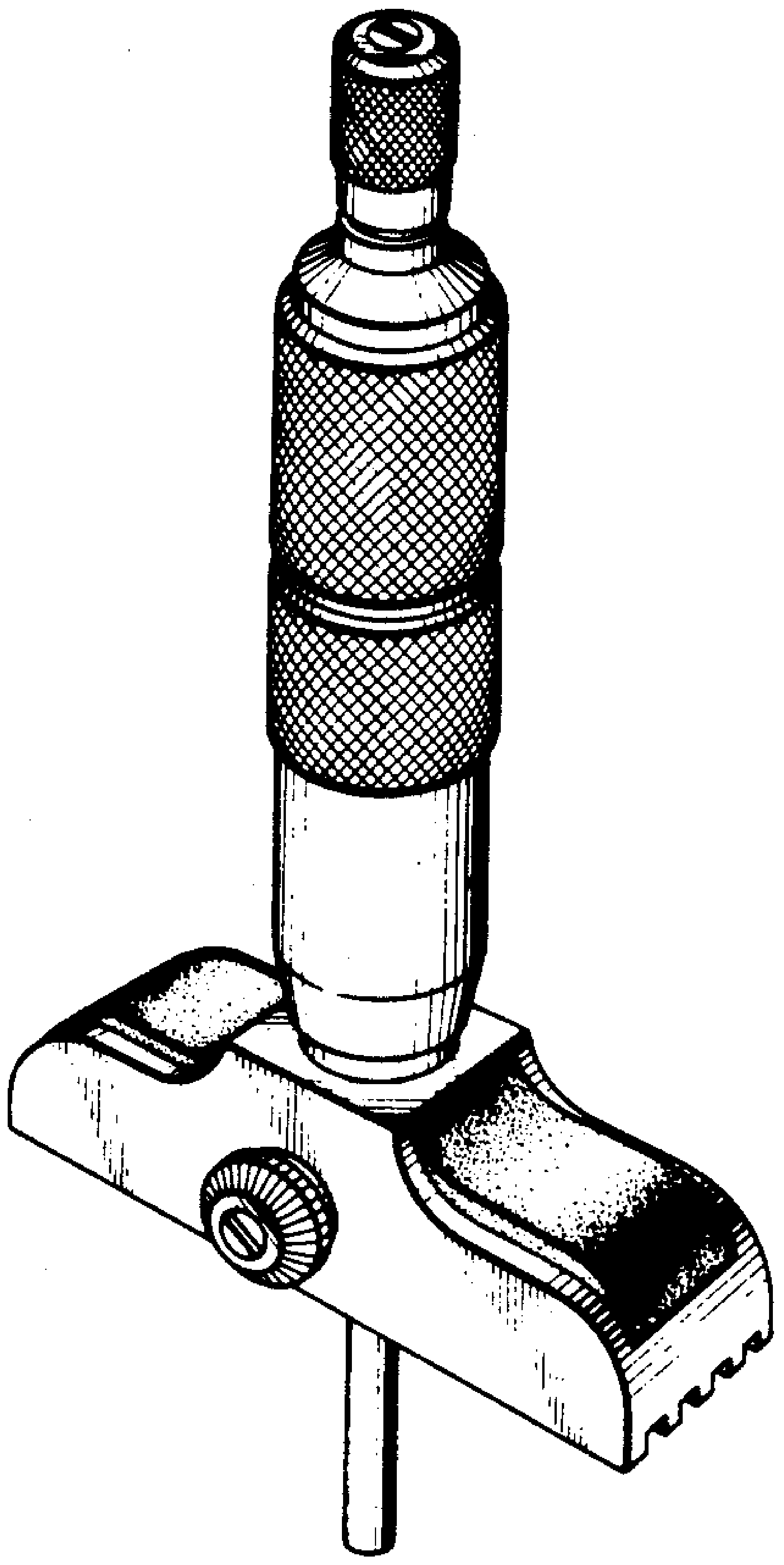
Attorney, Agent, or Firm—Koda and Androlia

[57] **CLAIM**

The ornamental design for a depth micrometer, substantially as shown and described.

DESCRIPTION

FIG. 1 is a right front perspective view of a depth micrometer showing my new design;
FIG. 2 is a top plan view thereof;
FIG. 3 is a bottom plan view thereof;
FIG. 4 is a left side elevational view thereof;
FIG. 5 is a rear elevational view thereof;
FIG. 6 is a front elevational view thereof;
FIG. 7 is a right side elevational view thereof.



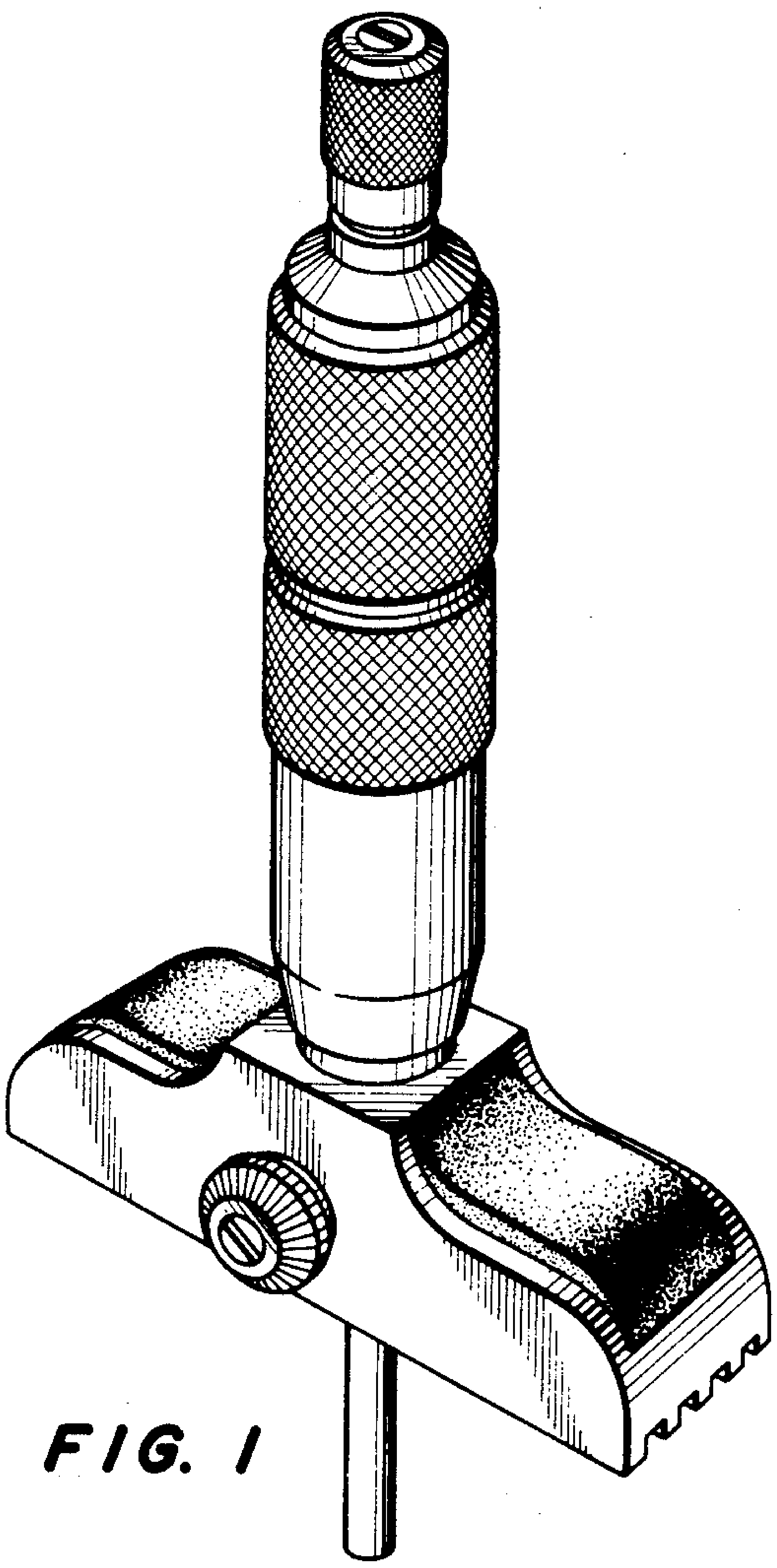


FIG. 1

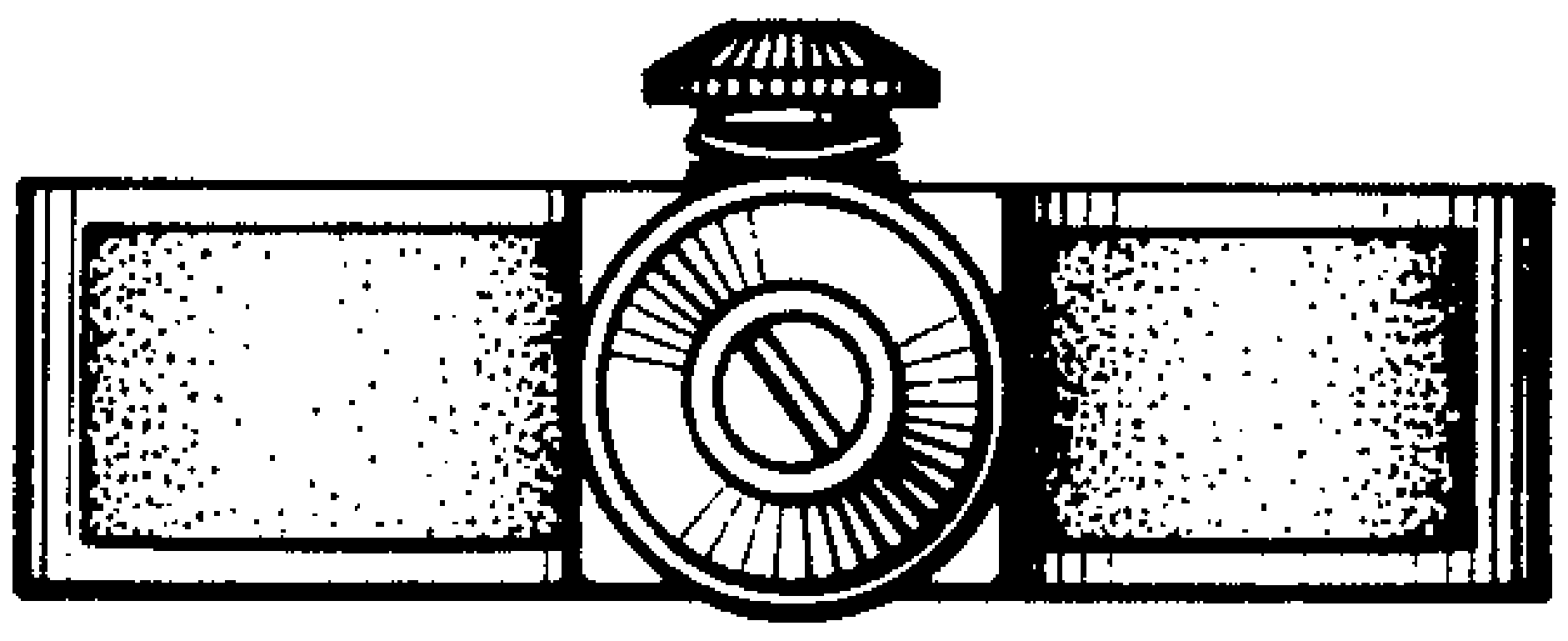


FIG. 2

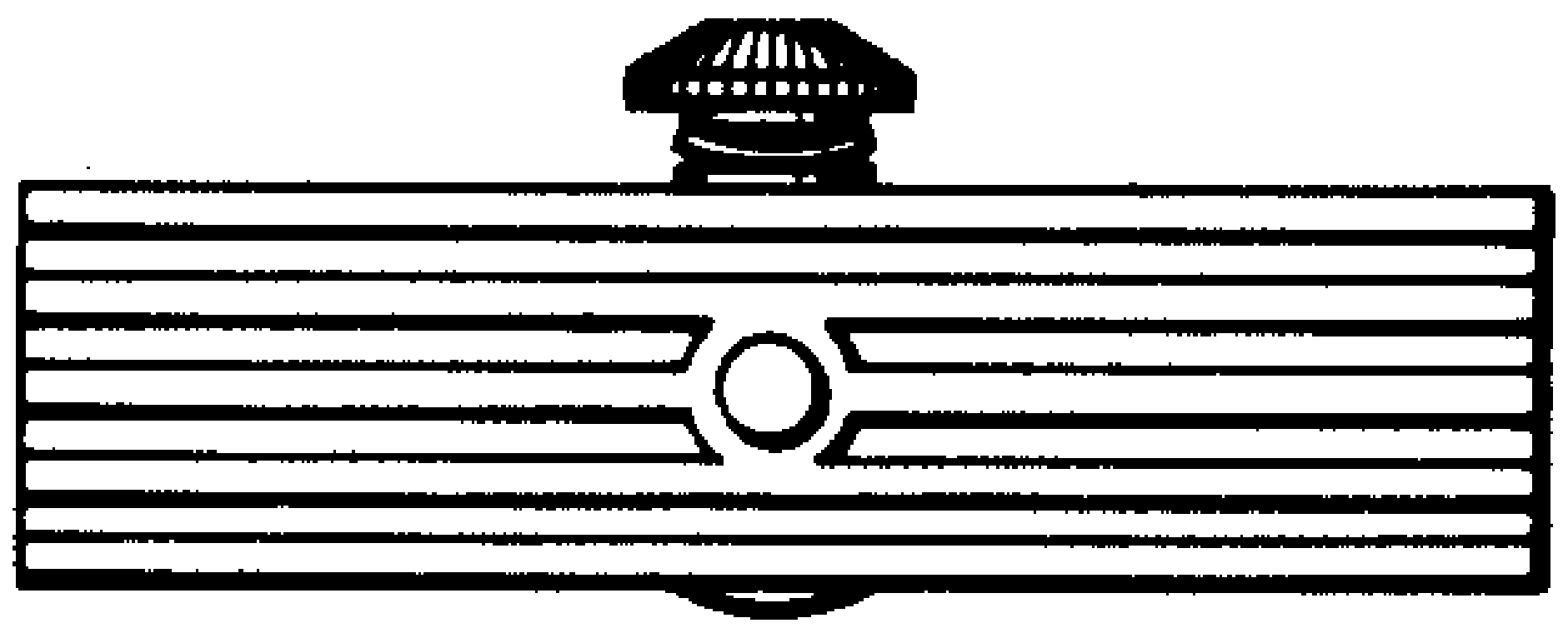


FIG. 3

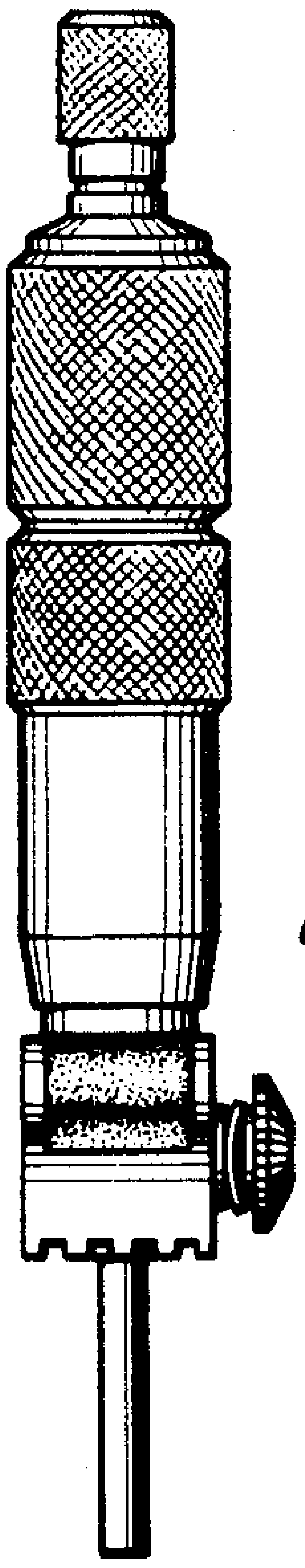


FIG. 4

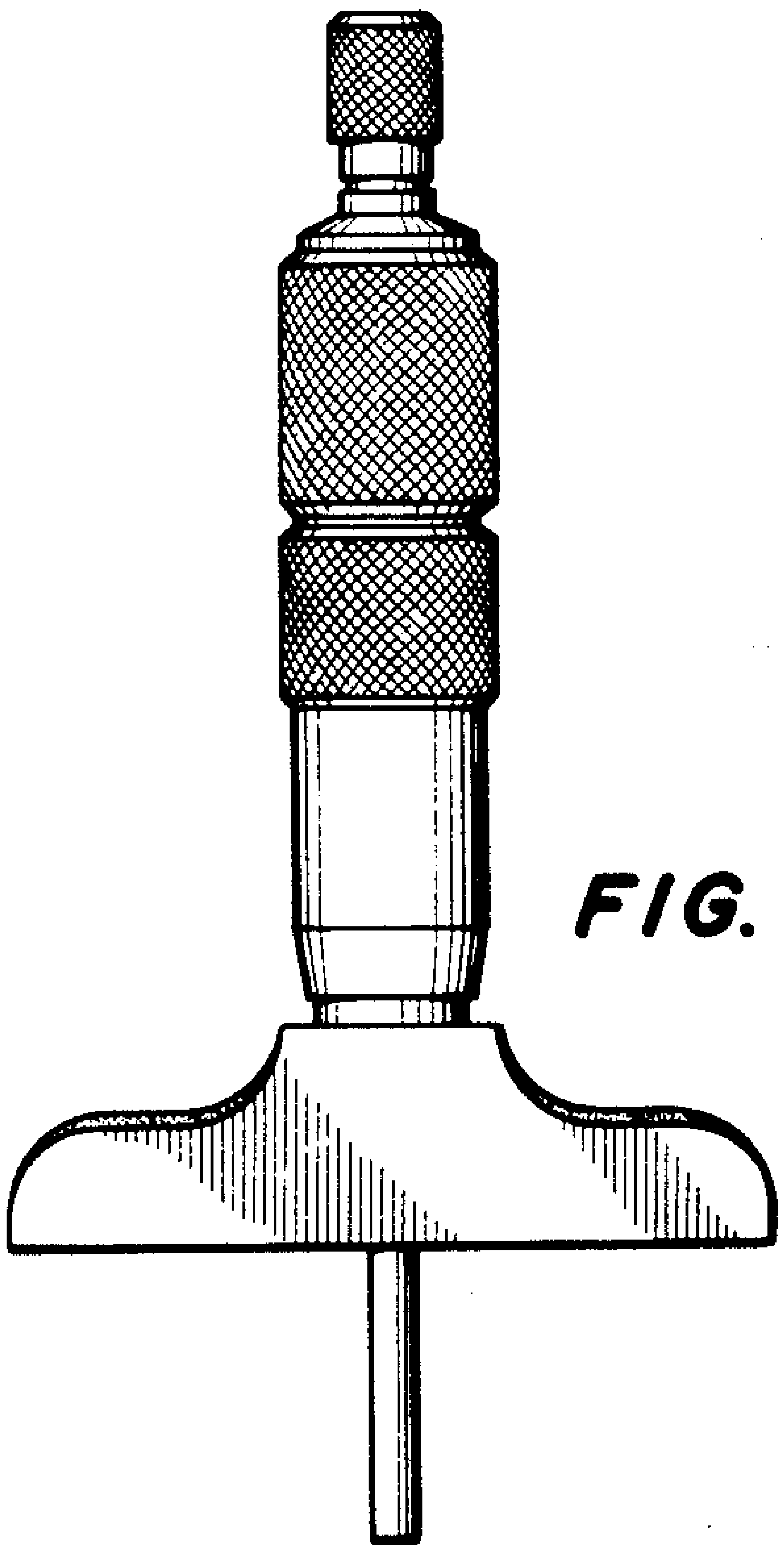


FIG. 5

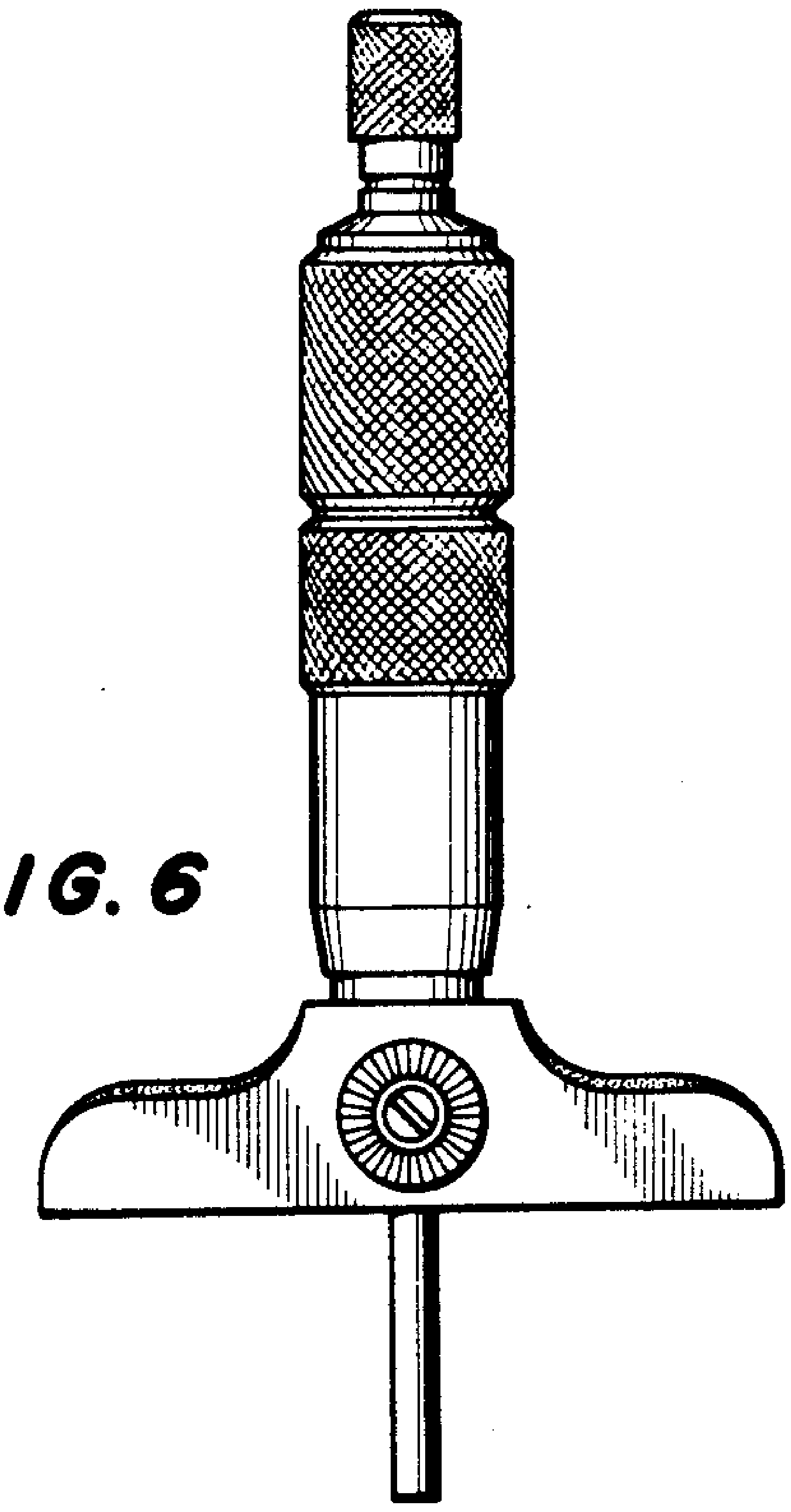


FIG. 6

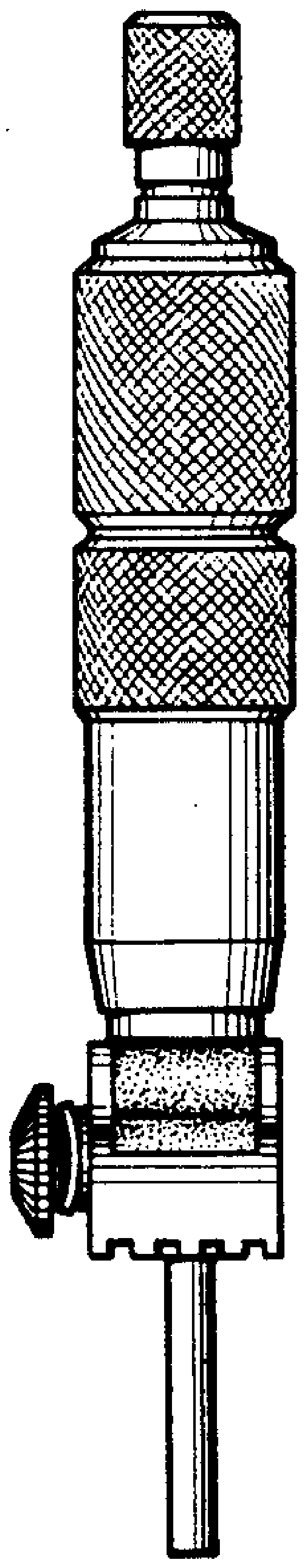


FIG. 7